

4 Chamber Plasma System



Anatech's multi chamber system allows plasma processing of up to four samples at one time while avoiding cross contamination.

Applications:
Ashing
Failure Analysis
Surface Modification
Biological Sample Ashing

4 Chamber Plasma System

Control System

Siemens S7-200 series PLC controller
Digital display for power, pressure, gas flow and time
Pass word protected
Gas Mass Flow Controller—1000 SCCM
Single gas input

Control Systems Options

Two program / two gases
Capacitance manometer
Slow pump and particle reduction
Throttle valve
Nitrogen Backfill

Reactor Chamber

System available with (2) or (4) chambers
4" Dia x 8" Quartz Chambers
Front loading
View port on front door with UV shield

RF Power Source

0-600 Watt, 13.56 MHz
Forward and reflected power reading
3% power regulation
Auto Match RF Tuner
Optional:
300 Watt 13.56 MHz supply
Low frequency optional

Power Requirements

115-VAC 15A 50/60-HZ
220-VAC optional
115-VAC 15A for Vacuum on separate

Dimensions

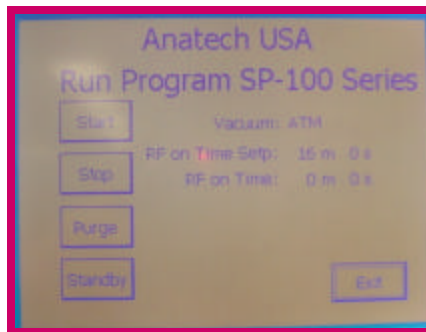
Cabinet Module:
23"W x 33"H x 30"D
Shipping Weight:
250 lbs Crated weight estimated

Vacuum Pump

23.3 CFM Standard—115 or 208V
Oxygen Preparation— Class "B"
Oil Mist Filter

Vacuum System Options

Corrosive service



Siemens S7-200 Series
"Touch Panel" Control
Pass word protected

CALL ANATECH USA TODAY TO DISCUSS YOUR APPLICATION

**ANATECH USA SYSTEMS
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